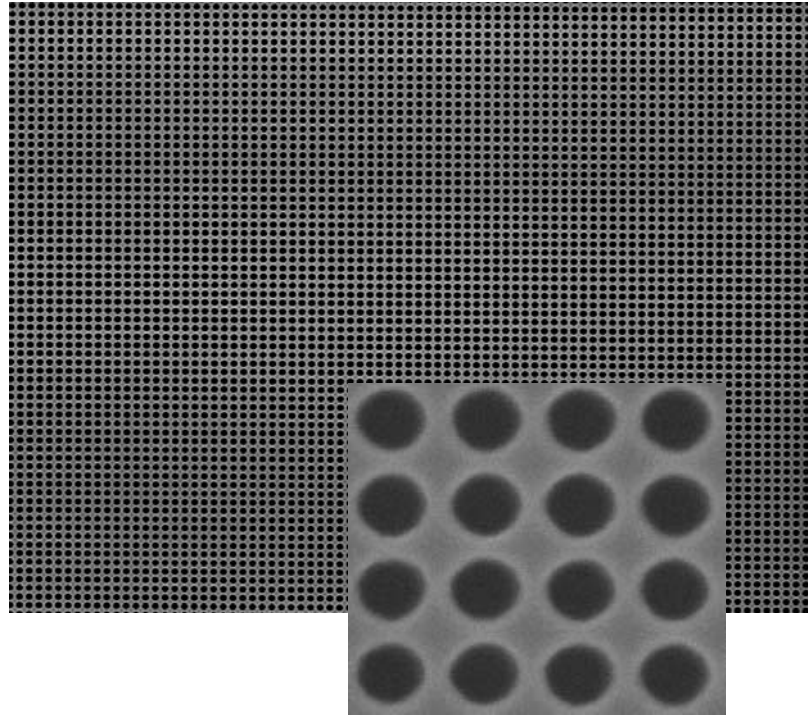


NANOIMPRINT TEMPLATE

45 nm HALF-PITCH NANOHOLE ARRAY

High-quality nanohole array by EUV Interference Lithography

- Nanoholes on a rectangular grid
- Horizontal/vertical pitch 100 nm / 90nm
- Field size 0.6 x 0.6 mm²
- Si chip size 15 mm x 15 mm
- Etch depth 70 nm
- Hole density 72 Gholes /inch²
- Anti-stick coating available



Applications

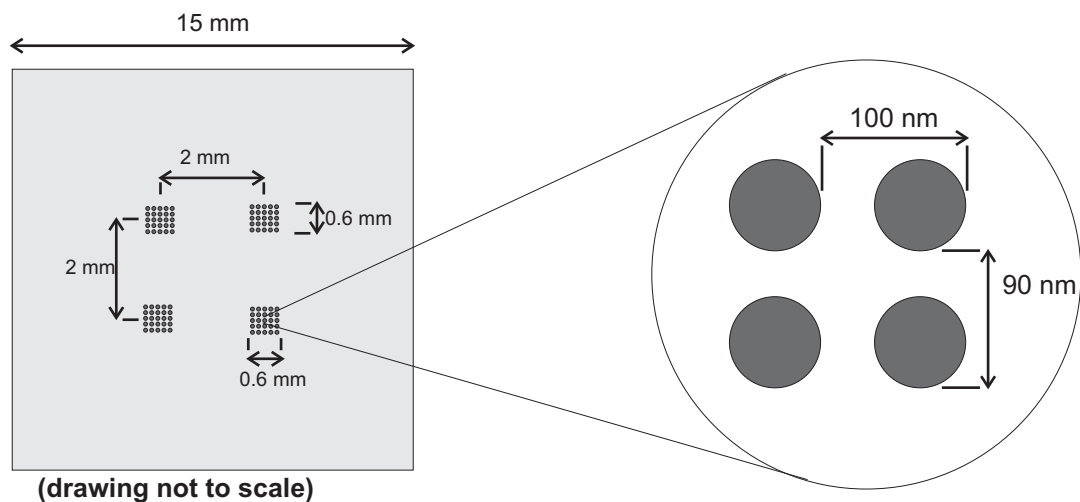
NIL process development

Nanophotonics

Nanomagnetics - data storage

Self-assembly templates

...



Larger area and custom-made templates available